

Amendments to the Claims

1. (Currently Amended): An Aboron and/or phosphorus doped silicon dioxide selective to undoped SiO_2 and Si_3N_4 etchant gas composition, comprising:

a carrier gas;

C_4F_6 ; at least one of C_4F_6 , C_3F_6 and C_5F_8 ;

CH_2F_2 ; and

a gas selected from the group consisting of CHF_3 , CF_4 , and mixtures thereof.

C 1
Claims 2 and 3 (Previously Canceled).

4. (Original): The etchant gas composition according to Claim 1, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

5. (Previously Amended): The etchant gas composition according to Claim 1, wherein the carrier gas comprises argon.

6. (Currently Amended): An A boron and/or phosphorus doped silicon dioxide selective to undoped SiO₂ and Si₃N₄ etchant gas composition, consisting essentially of:

a carrier gas;

C₄F₆; at least one of C₄F₆, C₃F₆ and C₅F₈;

CH₂F₂; and

CHF₃.

Claims 7 and 8 (Previously Canceled).

9. (Original): The etchant gas composition according to Claim 6, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

10. (Previously Amended): The etchant gas composition according to Claim 6, wherein the carrier gas comprises argon.

11. (Currently Amended): An A boron and/or phosphorus doped silicon dioxide selective to undoped SiO₂ and Si₃N₄ etchant gas composition, consisting essentially of:

a carrier gas;

C₄F₆; at least one of C₄F₆, C₃F₆ and C₅F₈;

CH₂F₂; and

CF₄.

C1
Claims 12 and 13 (Previously Canceled).

14. (Original): The etchant gas composition according to Claim 11, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

15. (Previously Amended): The etchant gas composition according to Claim 11, wherein the carrier gas comprises argon.

16. (Currently Amended): An A boron and/or phosphorus doped silicon dioxide selective to undoped SiO₂ and Si₃N₄ etchant gas composition, consisting essentially of:

a carrier gas;

C₄F₆; at least one of C₄F₆, C₃F₆ and C₅F₈;

CH₂F₂;

CHF₃; and

CF₄.

Claims 17 and 18 (Previously Canceled).

19. (Original): The etchant gas composition according to Claim 6, wherein the carrier gas is selected from the group consisting of argon, helium, and xenon.

20. (Previously Amended): The etchant gas composition according to Claim 16, wherein the carrier gas comprises argon.

Claims 21-64 (Previously Canceled).

65. (Previously Added): The etchant gas composition according to
Claim 1 comprising O₂.

66. (Previously Added): The etchant gas composition according to
Claim 1 comprising CO.

67. (Previously Added): The etchant gas composition according to
Claim 1 wherein the carrier gas comprises helium.

68. (Previously Added): The etchant gas composition according to
Claim 6 wherein the carrier gas comprises helium.

69. (Previously Added): The etchant gas composition according to
Claim 11 wherein the carrier gas comprises helium.

70. (Previously Added): The etchant gas composition according to
Claim 16 wherein the carrier gas comprises helium.

71. (Previously Added): The etchant gas composition according to
Claim 1 wherein the carrier gas comprises xenon.

72. (Previously Added): The etchant gas composition according to
Claim 6 wherein the carrier gas comprises xenon.

73. (Previously Added): The etchant gas composition according to Claim 11 wherein the carrier gas comprises xenon.

74. (Previously Added): The etchant gas composition according to Claim 16 wherein the carrier gas comprises xenon.

75. (New): The etchant gas composition according to Claim 1, comprising C_4F_6 .

76. (New): The etchant gas composition according to Claim 1, comprising C_3F_6 .

77. (New): The etchant gas composition according to Claim 1, comprising C_5F_8 .

78. (New): The etchant gas composition according to Claim 6, comprising C_4F_6 .

79. (New): The etchant gas composition according to Claim 6, comprising C_3F_6 .

80. (New): The etchant gas composition according to Claim 6, comprising C_5F_8 .

81. (New): The etchant gas composition according to Claim 11, comprising C₄F₆.

82. (New): The etchant gas composition according to Claim 11, comprising C₃F₆.

83. (New): The etchant gas composition according to Claim 11, comprising C₅F₈.

84. (New): The etchant gas composition according to Claim 16, comprising C₄F₆.

85. (New): The etchant gas composition according to Claim 16, comprising C₃F₆.

86. (New): The etchant gas composition according to Claim 16, comprising C₅F₈.